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(54) **Title:** METHOD TO MODIFY AN OPTICAL DEVICE RESIST

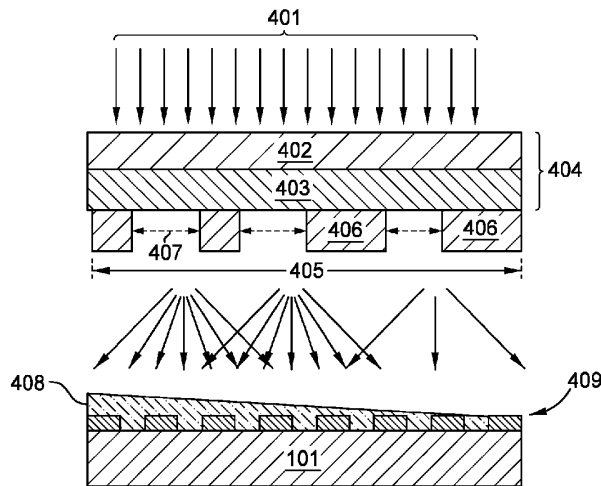


FIG. 4A

(57) **Abstract:** A method of optical device fabrication is described. The method includes identifying a graytone mask profile of a mask substrate. A graytone mask pattern of the mask substrate is generated, in which mask structures are disposed on a surface of the mask substrate, a diffuser, or a dose adjustment layer coupled to the surface of the mask substrate that correspond to the graytone mask pattern. An optical device resist is exposed by projecting a light through the graytone mask pattern that is disposed over an optical device substrate. The optical device resist has a varying thickness according to the graytone mask pattern after developing the optical device resist.

[Continued on next page]

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